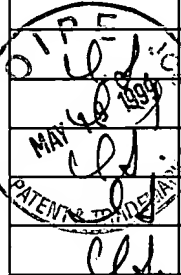


<b>FORM PTO-1449</b>			<b>Docket Number (Optional)</b> 008565-D7213		<b>Application Number</b> 09/218,997	
<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>			<b>Applicant</b> FUKAMI, Teruaki			
(Use several sheets if necessary)			<b>Filing Date</b> December 22, 1998		<b>Group Art Unit</b> 1744	
<b>U.S. PATENT DOCUMENTS</b>						
<b>EXAMINER INITIAL</b>	<b>DOCUMENT NUMBER</b>	<b>DATE</b>	<b>NAME</b>	<b>CLASS</b>	<b>SUBCLASS</b>	<b>FILING DATE IF APPROPRIATE</b>
cl	4,973,563	11/27/90	Prigge, et al.	—	—	
				—	—	
<b>FOREIGN PATENT DOCUMENTS</b>						
	<b>DOCUMENT NUMBER</b>	<b>DATE</b>	<b>COUNTRY</b>	<b>CLASS</b>	<b>SUBCLASS</b>	<b>TRANSLATION (YES/NO)</b>
	0 702 399	3/20/96	EP	—	—	
	0 665 582	8/2/95	EP	—	—	
	4-130100	5/1/92	JP	—	—	
	4-101418	4/2/92	JP	—	—	
	0 674 343	9/27/95	EP	—	—	
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>						
cl	Morinaga, et al. "A Model for the Electrochemical Deposition and Removal of Metallic Impurities on Si Surfaces," IEICE Trans. Electron., Vol. E79-C. No. 3, March 1996, pp. 343 – 362.					
cl	Ohmi, et al. "Metallic Impurities Segregation at the Interface Between Si Wafer and Liquid during Wet Cleaning," J. Electrochem. Soc., Vol. 139 (1992), No. 11, November 1992, pp. 3317 – 3335.					
<b>EXAMINER</b> <i>Edward L. Smith</i>		<b>DATE CONSIDERED</b> 9/27/00				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.						

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